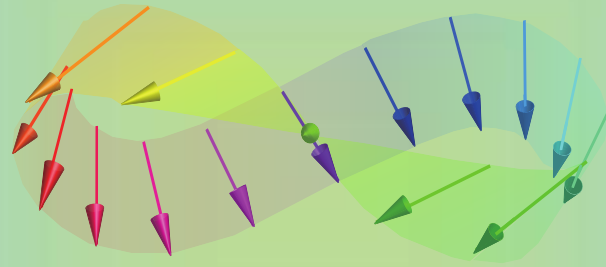


Heusler Alloy Films for Spintronic Devices



Atsufumi Hirohata

THE UNIVERSITY *of York*





Where is York ?



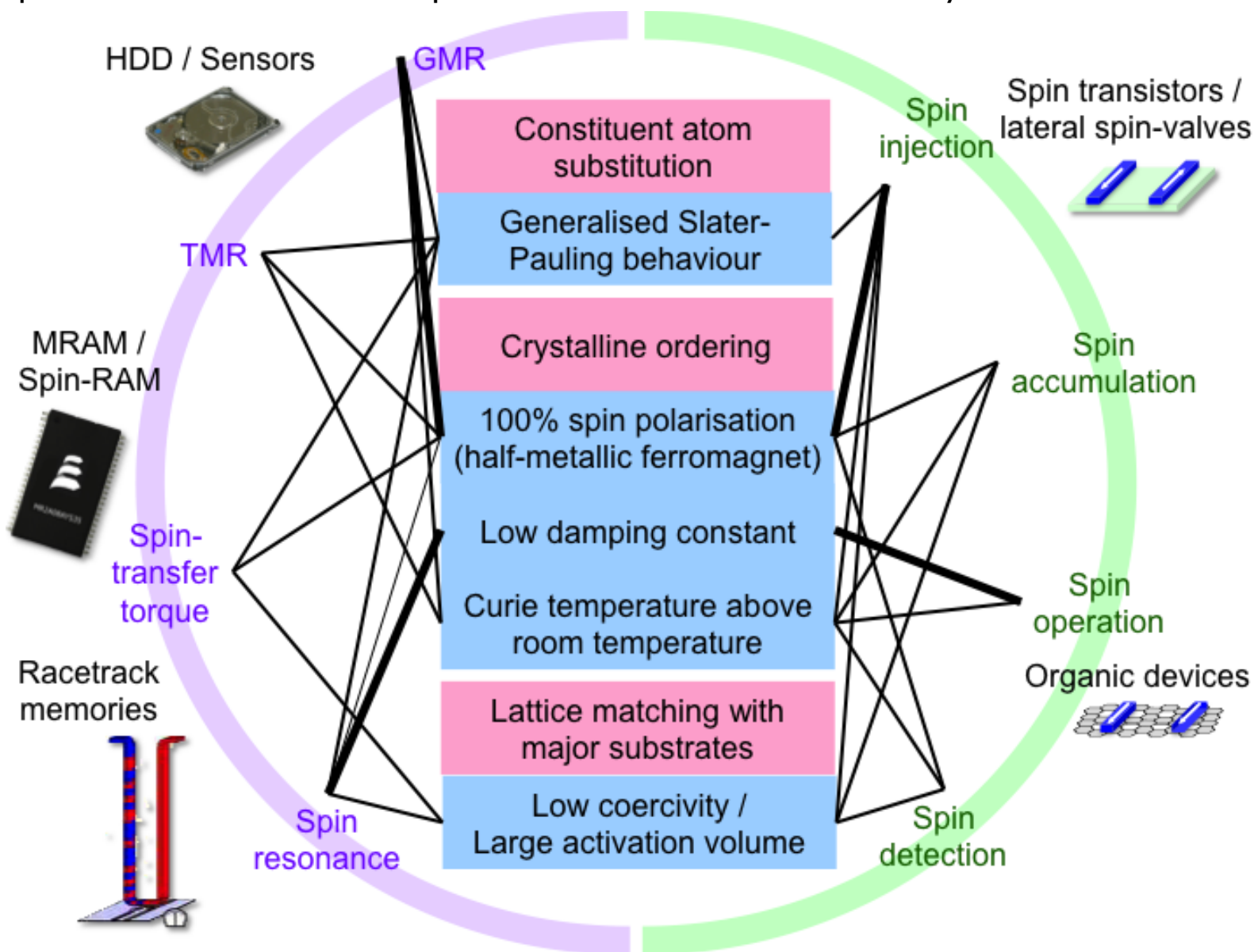
Edinburgh

York

London

Applications for Heusler Alloys

Requirements for device implementations for Heusler alloys :

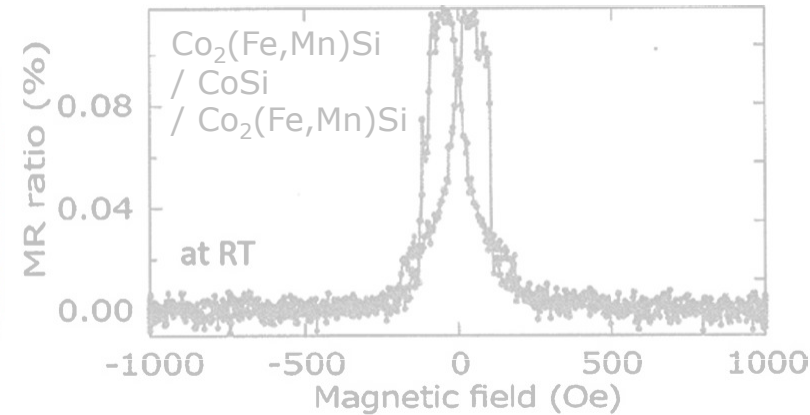
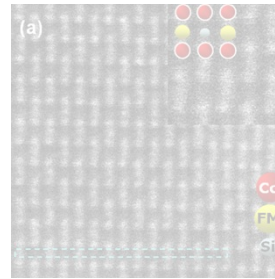




Possible Solutions

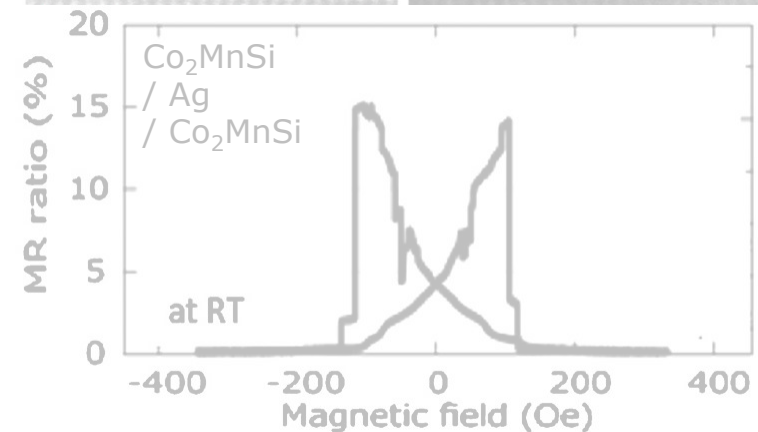
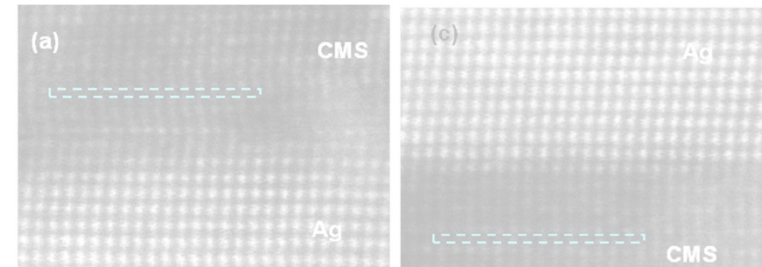
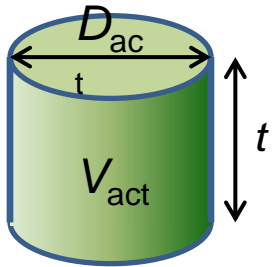
Smoothing the interfaces :

- Optimisation of the non-magnetic spacer
 - Ag
- Atomically sharp interface achieved
 - GMR ratio : $\sim 15\%$



Elimination of minor domains :

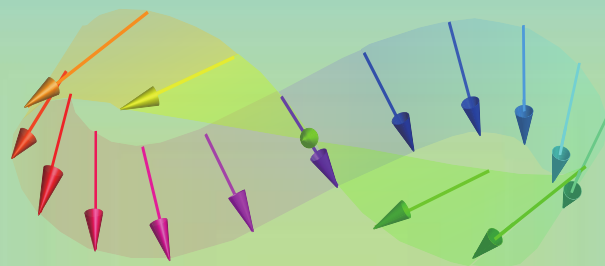
- Maximisation of **activation volume**
 - smallest volume that reverses in a single step



Minimisation of intermixing / deformation :

- **Low-temperature annealing** for Heusler alloy films
 - *in situ* TEM observation

Activation Volumes in Heusler Alloy Films



J. Sagar,¹ H. Sukegawa,² L. Lari,^{1,3} V. K. Lazarov,¹ S. Mitani,²
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³ *York* **JEOL** Nanocentre



EPSRC EP/H026126/1

Engineering and Physical Sciences
Research Council

Co₂FeSi Heusler-Alloy Epitaxial Film Growth



- Sample Structure:

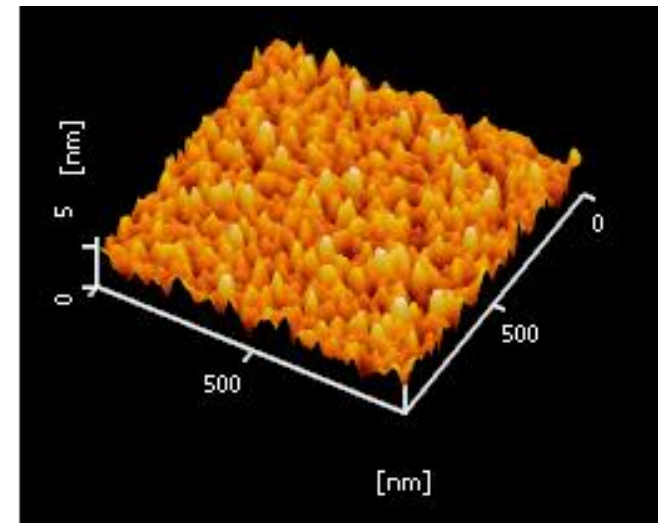
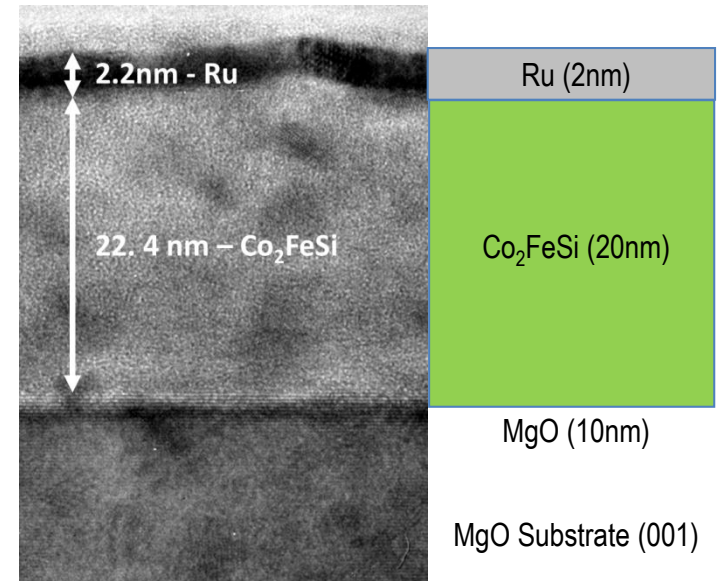
MgO [100]//MgO (10nm) / Co₂FeSi (2nm) / Ru (2nm)

- MgO substrate annealed at 800°C before deposition of a 10 nm MgO buffer layer and annealing again at 400°C.

- Co₂FeSi deposited by UHV magnetron sputtering with base pressure of better than 3×10^{-7} Pa at a rate of 0.03 nm/s

- Post deposition AFM measurements of samples found R_a to be 4.7 nm

- *Ex-situ* post deposition annealing at 400°C, 500°C and 600°C to cause recrystallisation into B2 and $L2_1$ phases.





XRD Structural Characterisation

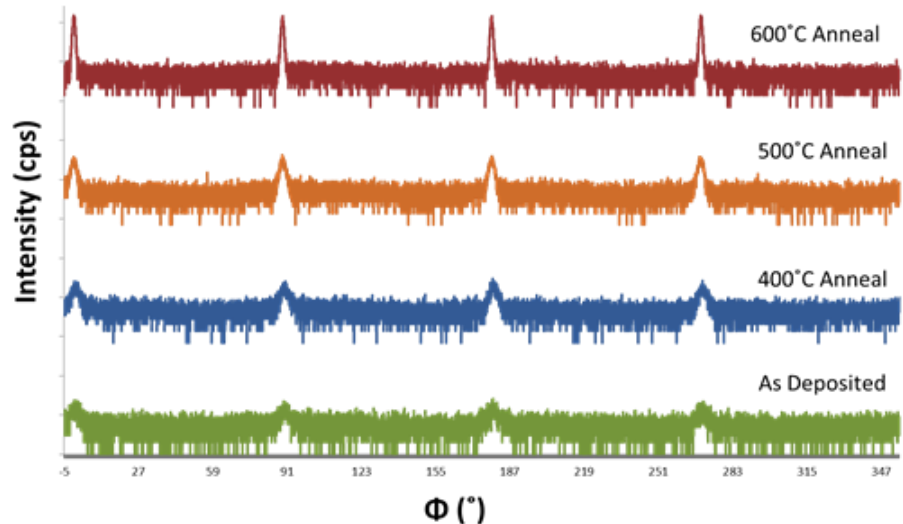
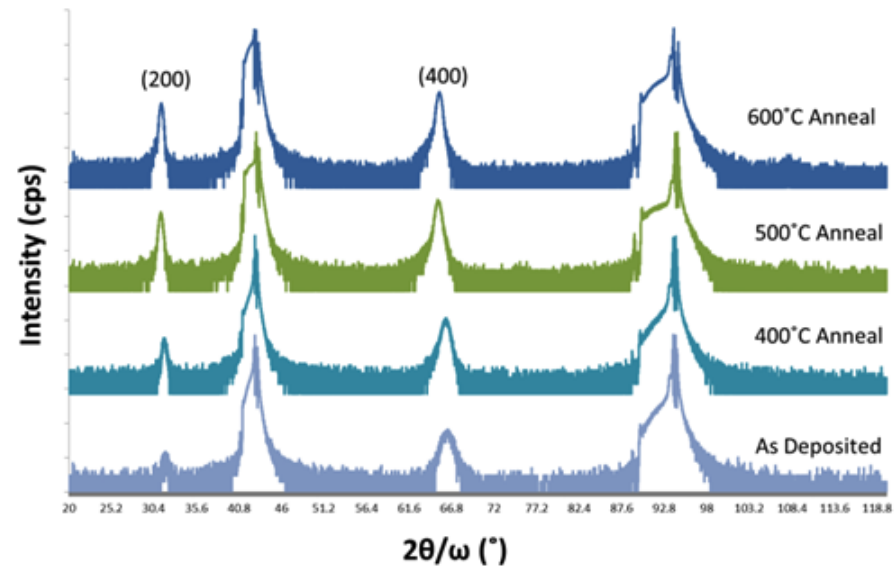
- X-ray diffraction (XRD) spectra were taken for as-deposited and post annealed films.

- $2\theta-\omega$ (out-of-plane) and $2\theta-\phi\chi$ (in plane) scans have been taken.

- This allows for structural characterisation and identification of order phases.

- Increasing intensity (200) and (400) peaks are characteristic of $B2$ and $L2_1$ ordering.

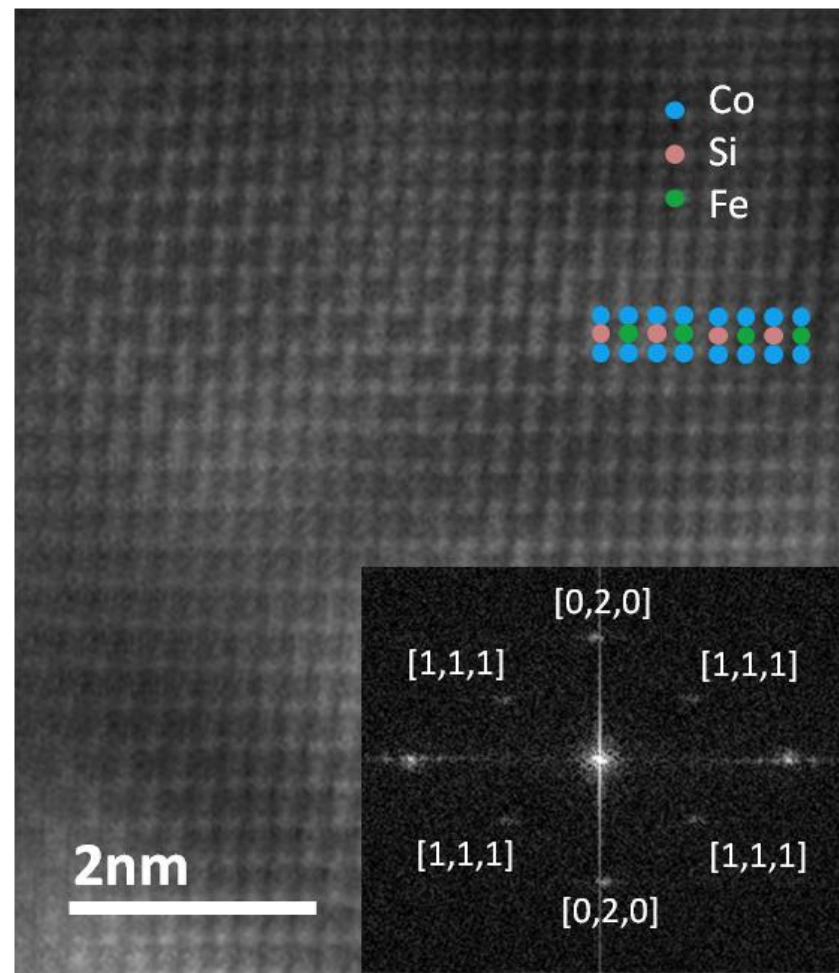
- Increased intensity (111) peaks in the $2\theta-\phi\chi$ show increased $L2_1$ ordering with increasing anneal temperature.





STEM Structural Characterisation

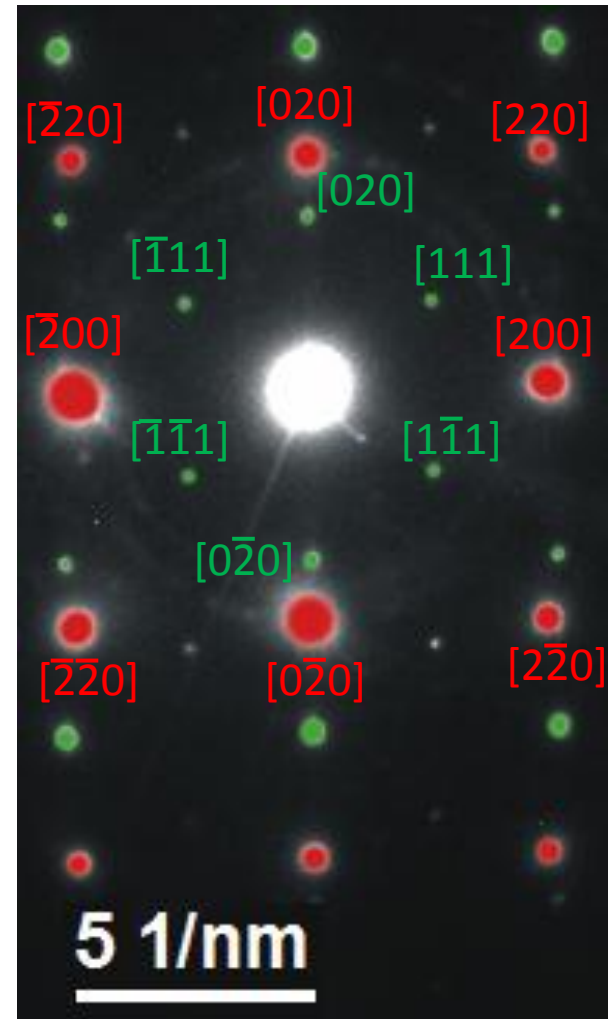
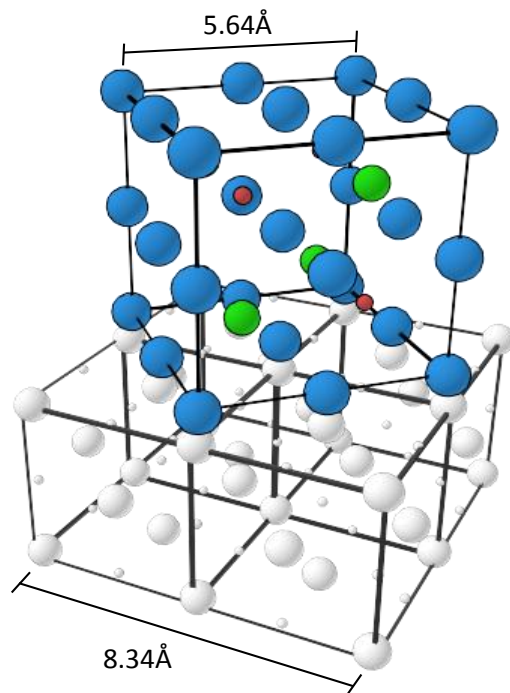
- HAADF STEM imaging with elemental contrast can be used for structural analysis of Heusler alloy films
- Using digital diffractograms and measurements of inter-atomic spacing, the in-plane and out-of-plane lattice constants have been found.
- From the [111] spots the in-plane lattice constant was found to be $(5.74 \pm 0.05) \text{ \AA}$ compared with the bulk value of 5.64 \AA
- From the [200] spots the out-of-plane lattice constant was found to be slightly reduced at $(5.44 \pm 0.05) \text{ \AA}$
- The volume of the unit cell was found to lie within error of the bulk value.





Co₂FeSi Heusler-Alloy Film Growth

- The lattice constant for Co₂FeSi is 5.64 Å and for MgO is 4.17 Å, this is a mismatch of 35%.
- To compensate for this mismatch the Co₂FeSi unit cell is found to rotate by 45° to align the Co₂FeSi [110] planes with the MgO [100].
- This rotation allows the Co₂FeSi to span two MgO unit cells and reduces the mismatch to 4.5%.

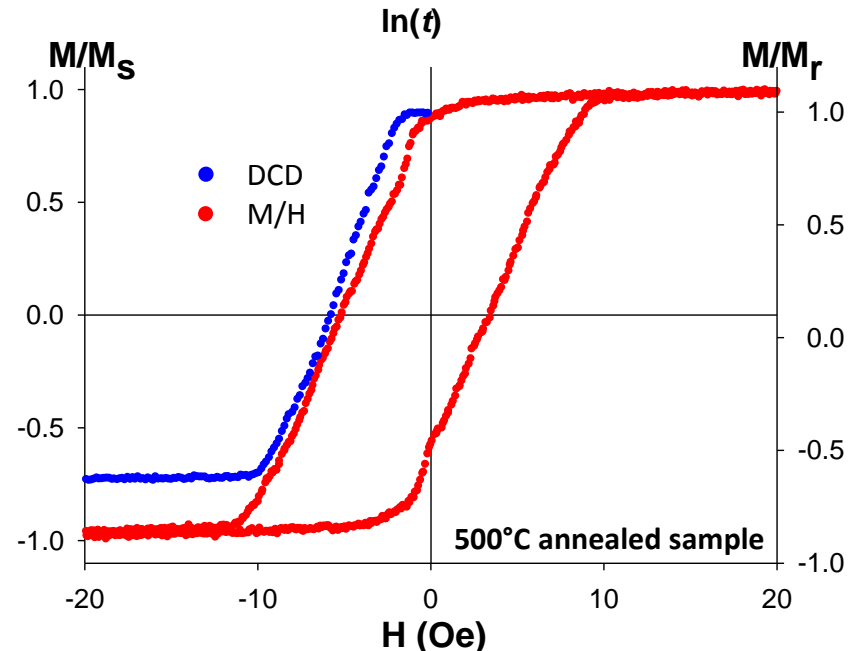
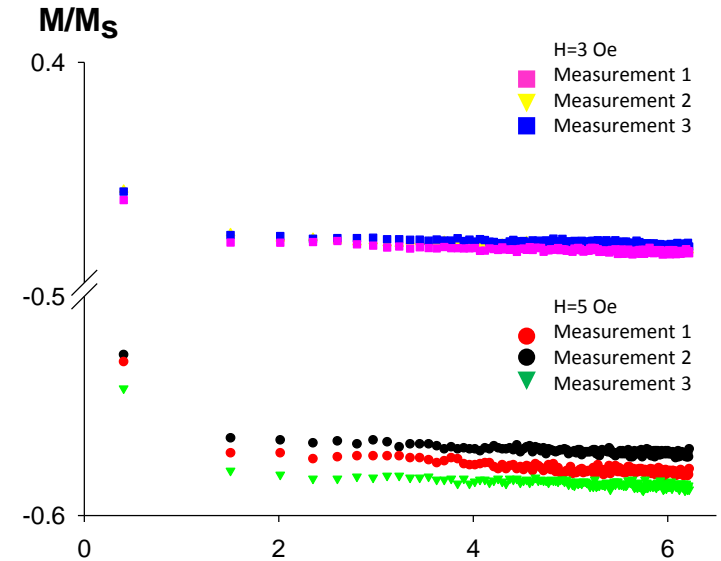


False colour diffraction pattern showing Co₂FeSi [110] and MgO [100] reflections.

Magnetic Time Dependence



- Magnetic time dependence measurements have been taken over the switching region.
 - These measurements are used to find a value for the magnetic viscosity $S_1(H)$ of each sample.
- $$\frac{-dM(H)}{d \ln t} = S_0 + S_1(H) \ln t + (S_2(H) \ln t)^2 + \dots$$
- DC demagnetised (DCD) remanence curves have also been taken for each sample.
 - For a DCD curve the sample is saturated, then the remanent magnetisation (M_r) is measured at increasing values of negative field.





Fluctuation Field

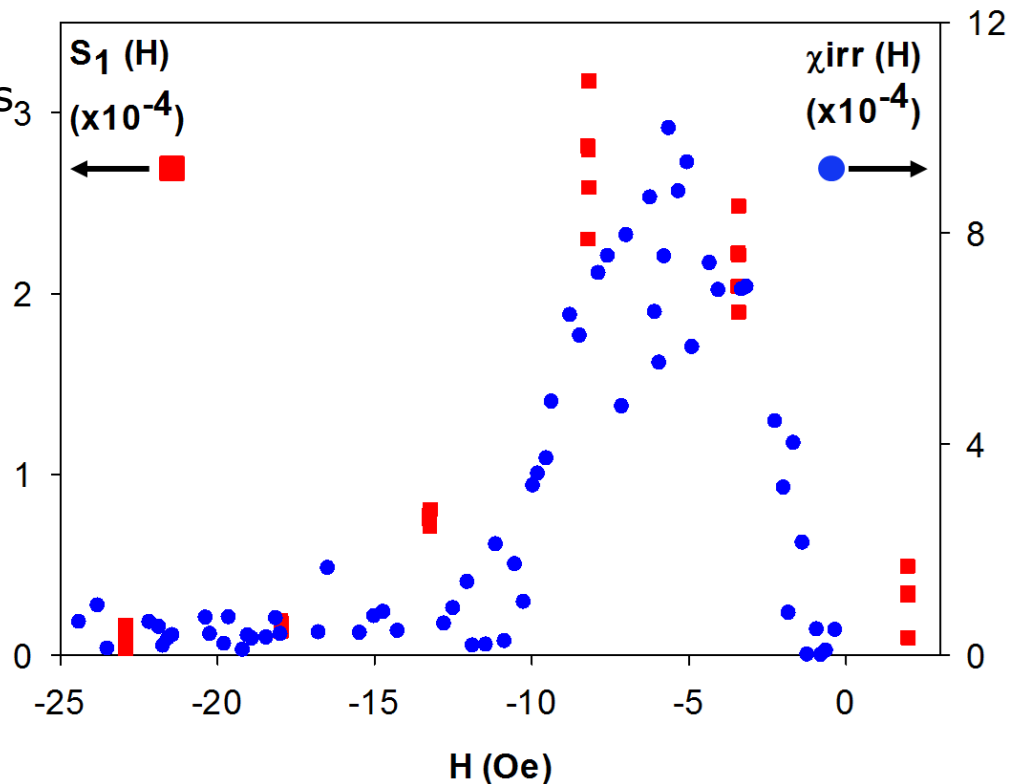
- The fluctuation field (H_f) is an imaginary field representing the effect of thermal energy.*

- The differential of the DCD curve gives the irreversible susceptibility (χ_{irr}).

$$\chi_{irr}(H) = \frac{d(DCD(H))}{dH}$$

- This can be combined with the value for $S_1(H)$ to give the fluctuation field (H_f).

$$H_f = \frac{S_1(H)}{\chi_{irr}(H)}$$



* L. Néel, *Ann. Geophys.* **5**, 99 (1949).



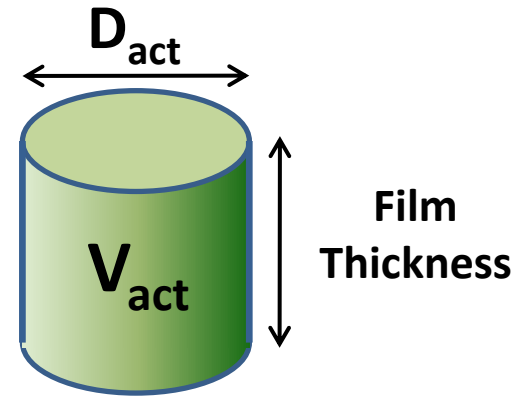
Estimated Activation Volumes

- H_f then gives rise to the concept of the activation volume (V_{act}) : *

$$V_{act} = \frac{k_B T}{M_s H_f}$$

- V_{act} is defined as the smallest volume that reverses in a single step.

- V_{act} is a relative measure because the value of M_s is unsure.



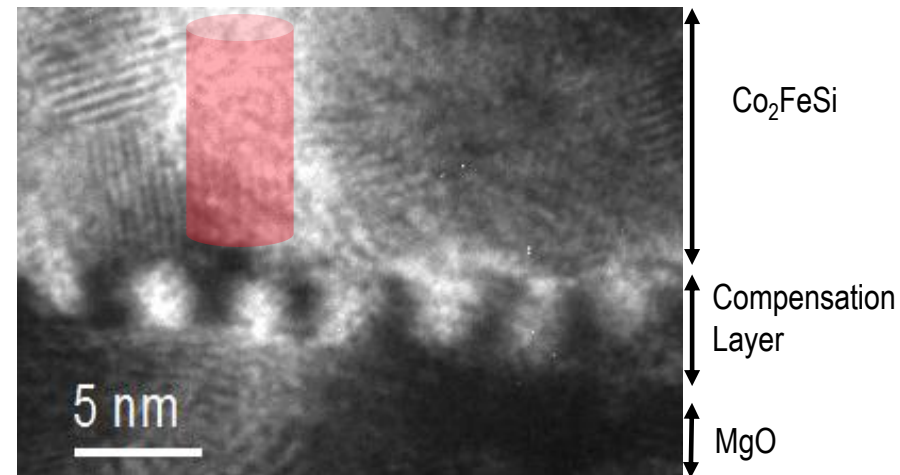
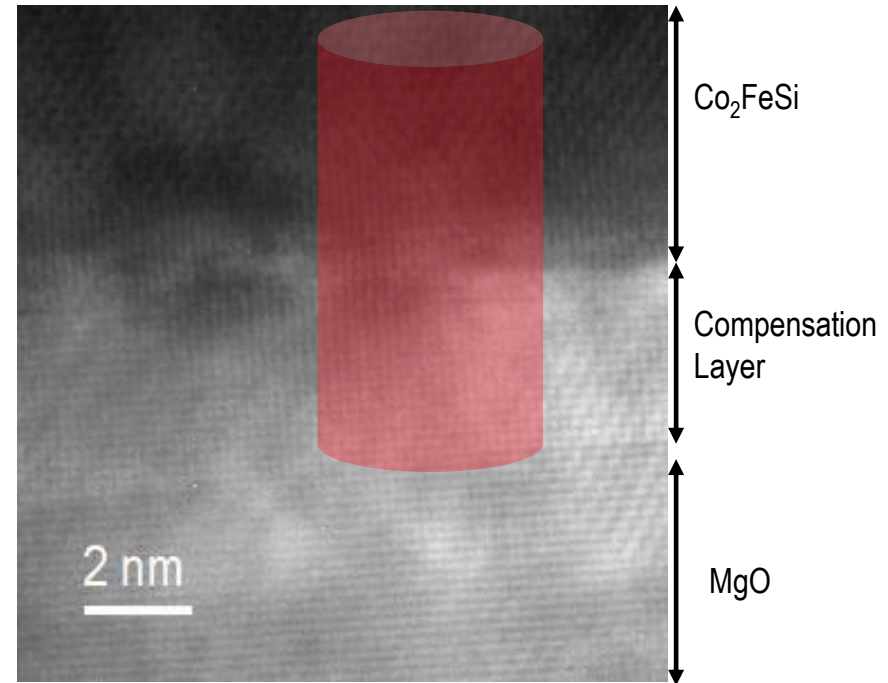
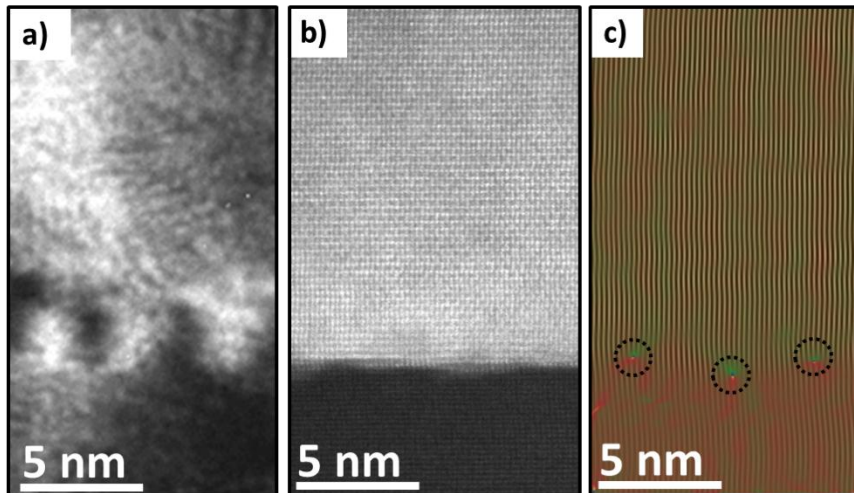
Annealing Condition	M_s ($\pm 0.1 \text{ emu/cc} \times 10^4$)	V_{act} ($\pm 0.5 \times 10^{-17} \text{ cm}^3$)	D_{act} ($\pm 0.5 \text{ nm}$)	H_c ($\pm 0.1 \text{ Oe}$)
As – deposited	4.4	4.0	5.0	2.9
400°C	5.2	1.6	3.2	1.7
500°C	4.5	4.5	5.3	4.5
600°C	4.8	4.6	5.4	7.2

* E. P. Wohlfarth, *J. Phys. F: Met. Phys.* **14**, 155 (1984).



Activation Volume in Epitaxial Co_2FeSi

- **Activation volume** was estimated to be ~ 4.0 nm.
- A lattice mismatch of 4.5 % to be compensated between MgO and Co_2FeSi .
- This compensation layer (periodic contrast) can be seen in the contrast change in the TEM image due to an increase in lattice spacing through this layer.
- This contrast change is due to compensation through the Co_2FeSi missing entire MgO planes to improve the epitaxy.



Pinned / Unpinned Domain Wall

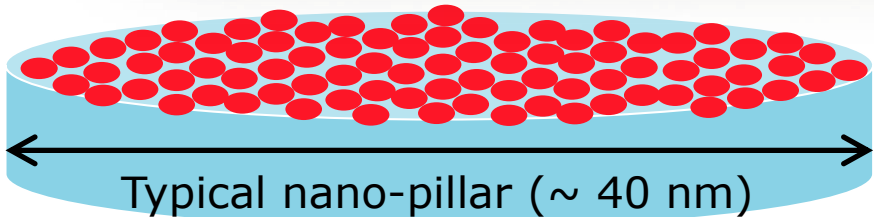
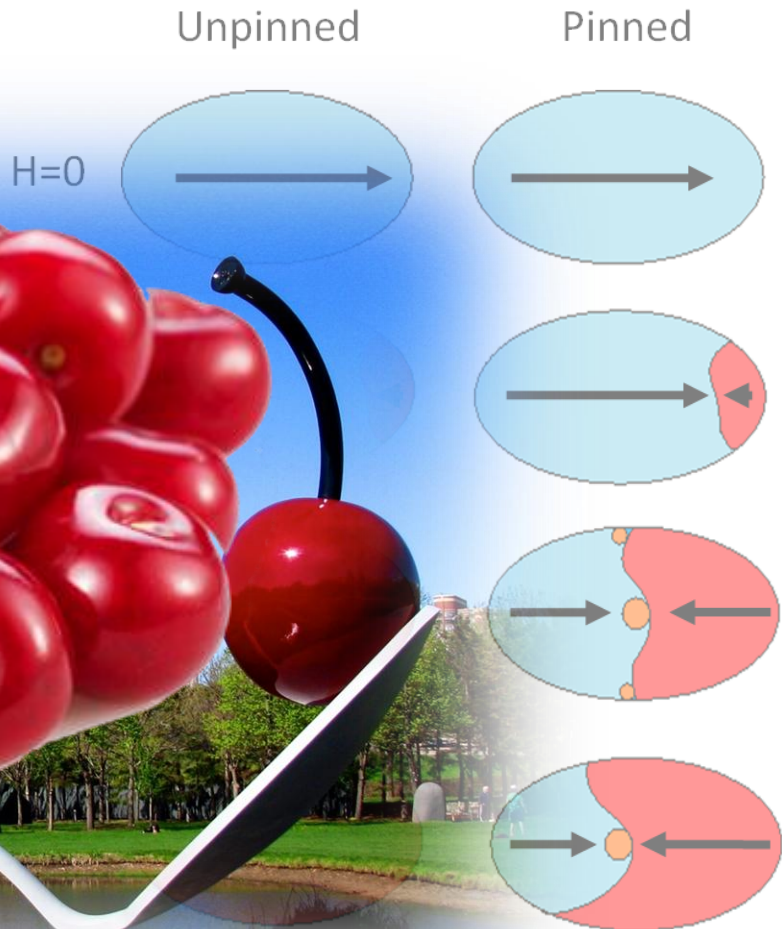
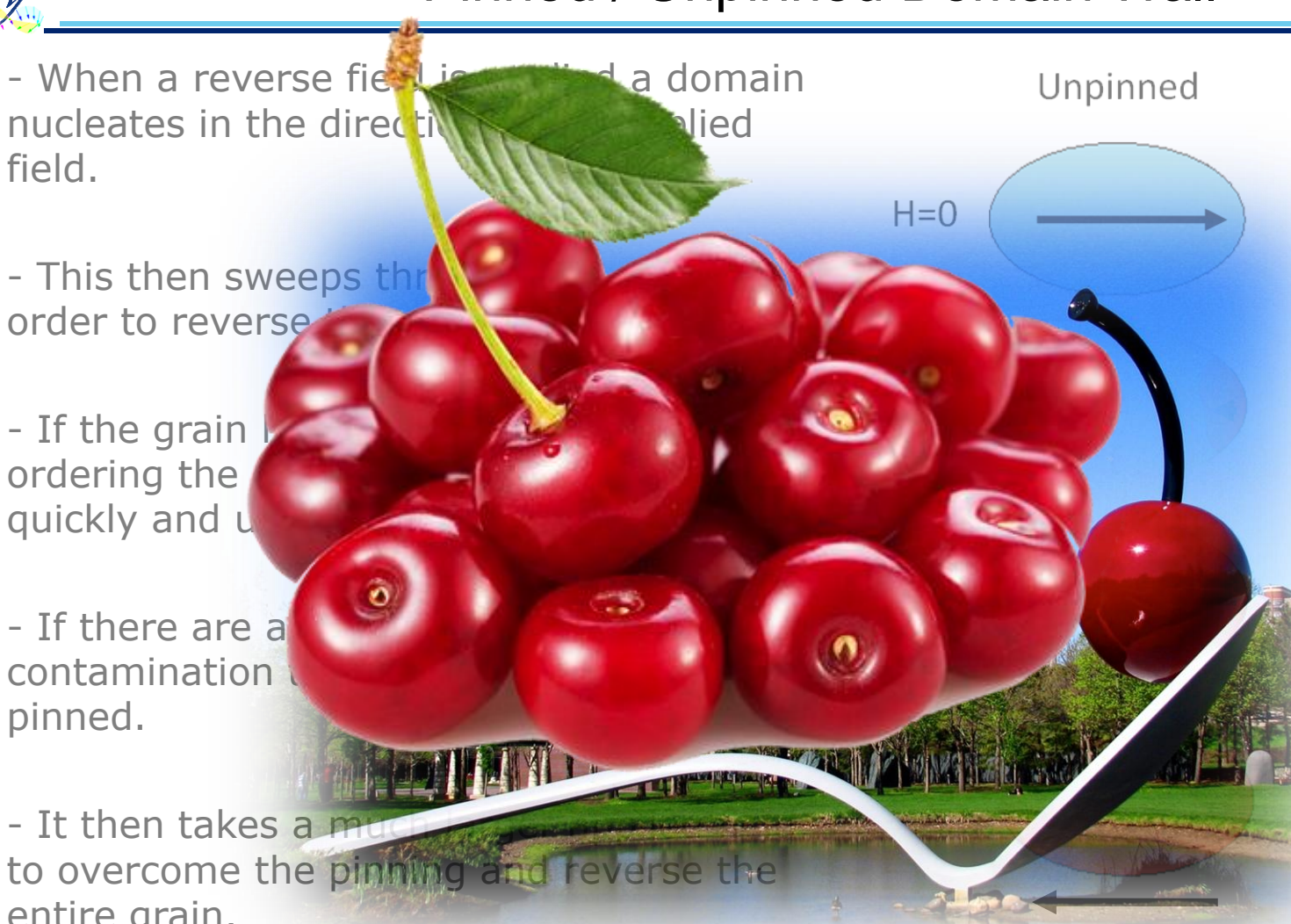
- When a reverse field is applied a domain nucleates in the direction of the applied field.

- This then sweeps through the grain in order to reverse the magnetization.

- If the grain is free of impurities, ordering the domain wall quickly and uniformly.

- If there are impurities or contamination, the domain wall is pinned.

- It then takes a much longer time to overcome the pinning and reverse the entire grain.



~ 25 pinning sites (epitaxial)

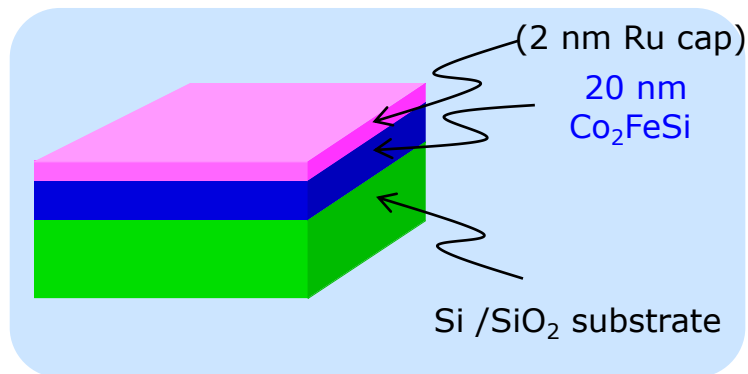
* J. Sagar et al., *Appl. Phys. Lett.* **101**, 102410 (2013).



Heusler-Alloy Film Growth

Sputter film deposition : *

- Controlled plasma HiTUS sputtering system
- Optimised target composition (e.g., $\text{Co}_{1.748}\text{Mn}_{1.118}\text{Si}_{1.134}$)
- Base pressure : $< 3.0 \times 10^{-5}$ Pa
- MgO (001) substrate cleaning :
acetone bath for 10 min. +
in situ heat treatment at 573 K for 20 min.
- Plasma :
RF field at 3.0×10^{-1} Pa Ar pressure
DC bias steering from -250 to -990 V to change the grain size
- Annealing at 760 K for 3 h (1st anneal)
followed by further annealing at 760 K for another 3 h (2nd anneal)
additional annealing at 760 K for 3 h (3rd anneal)



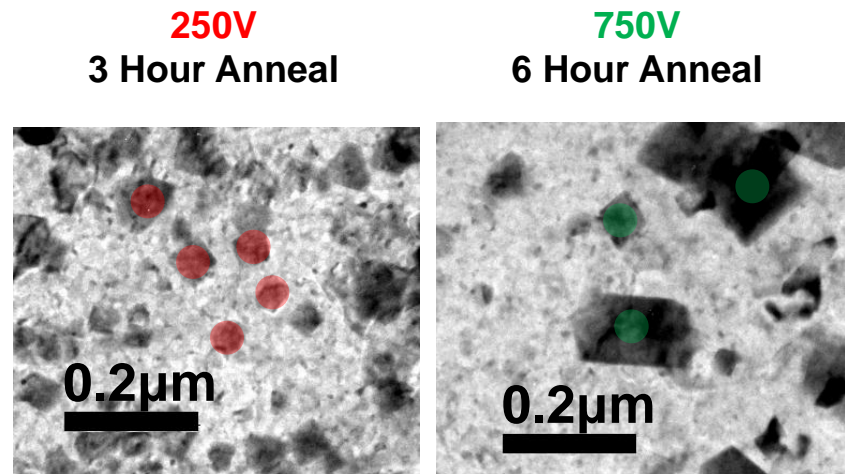
Magnetic / structural measurements :

- Princeton AGFM Model 2900
- ADE Model 10 VSM
- JEOL JEM-2011 TEM
- JEOL JEM-2200FS HR-(S)TEM

* A. Hirohata *et al.*, *Appl. Phys. Lett.* 95, 252506 (2009).

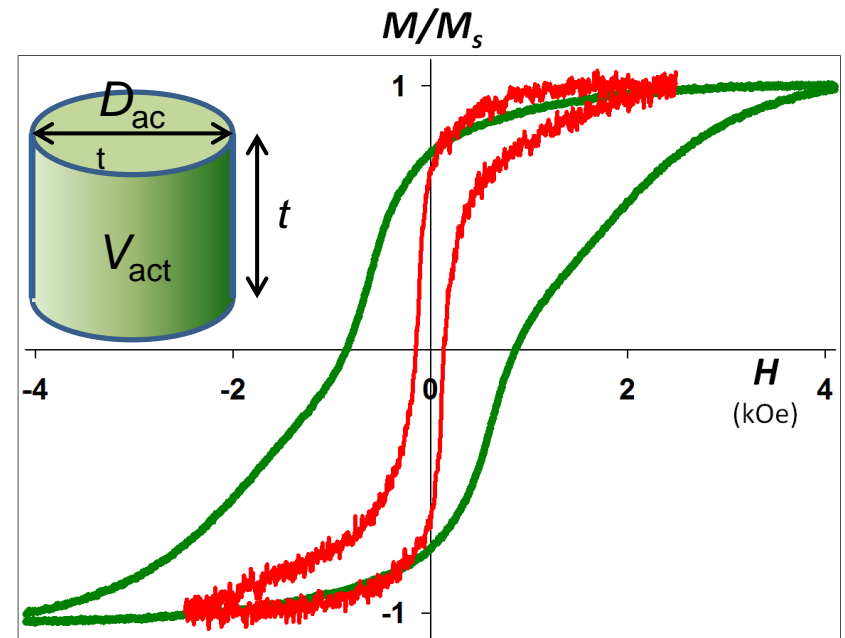
Activation Volume in Polycrystalline Co_2FeSi

- The activation volume has been shown to be bias voltage independent ($\sim 40 \text{ nm}$), but varies with annealing time.
- The physical grain volume is shown to increase with bias voltage and vary with annealing time.
- For films deposited at higher bias voltages the activation volume was 40% of the physical volume the particles are therefore multi-domain.
- Polycrystalline films can offer a "pinning-site-free" nano-pillar.



● = D_{act} 250V

● = D_{act} 750V

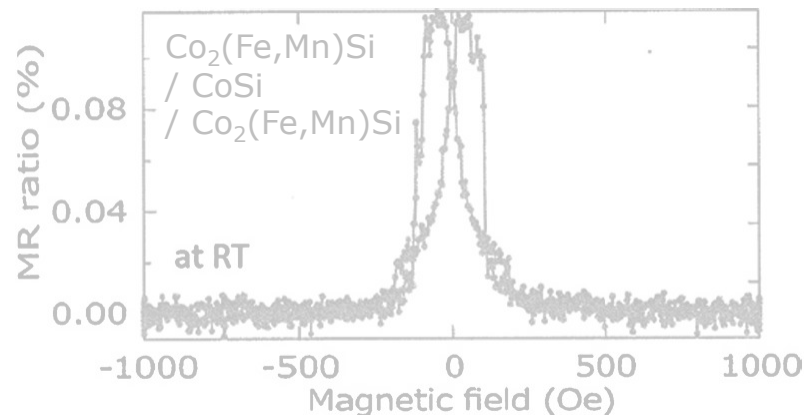
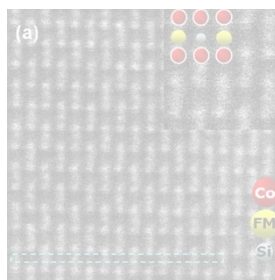




Possible Solutions

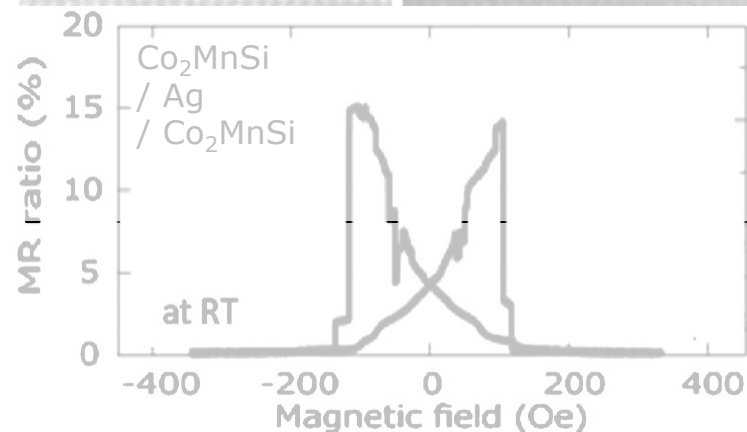
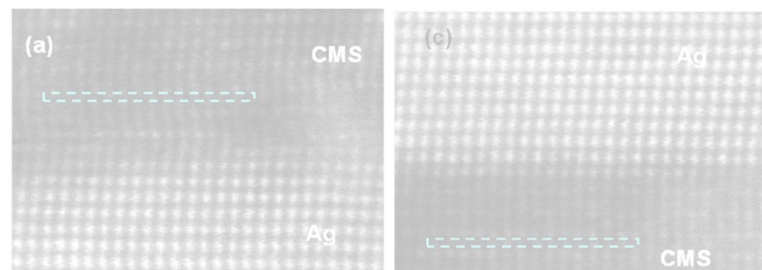
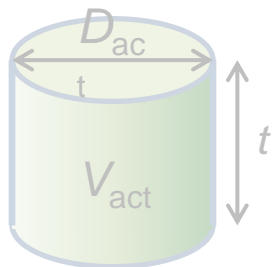
Smoothing the interfaces :

- Optimisation of the non-magnetic spacer
 - Ag
- Atomically sharp interface achieved
 - GMR ratio : $\sim 15\%$



Elimination of minor domains :

- Maximisation of **activation volume**
 - smallest volume that reverses in a single step



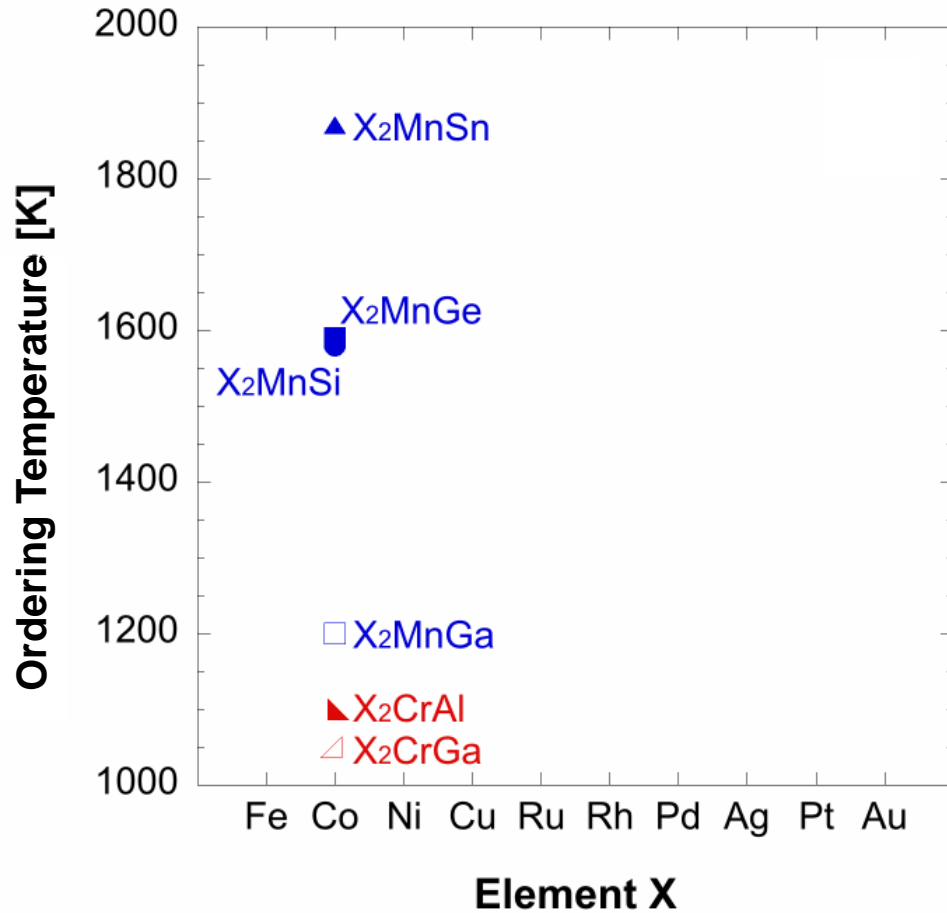
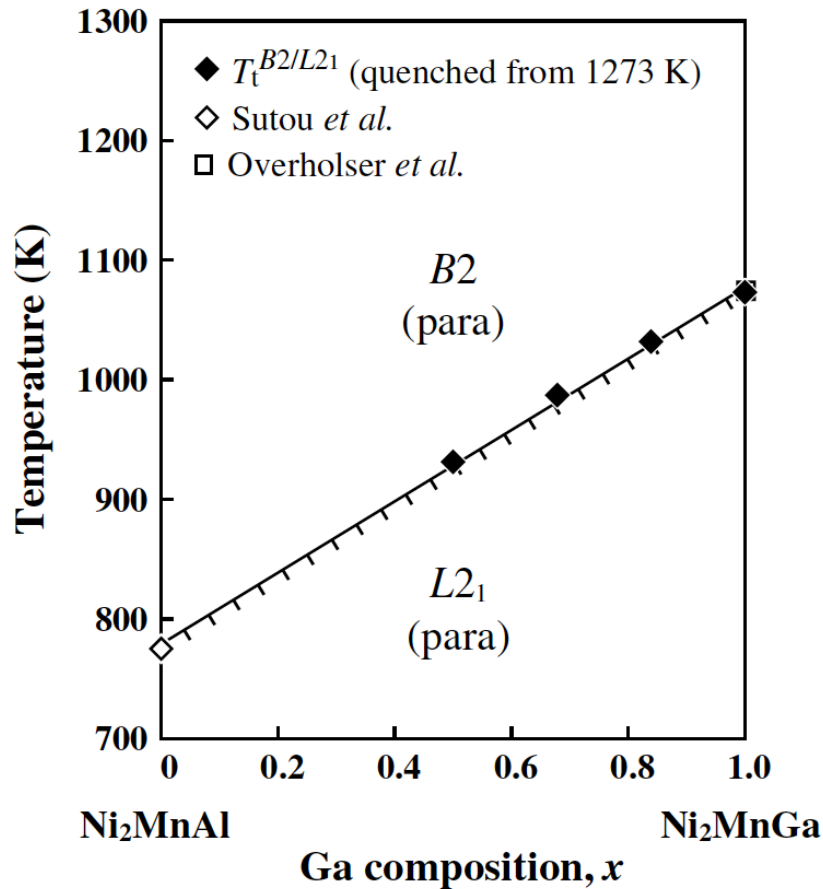
Minimisation of intermixing / deformation :

- **Low-temperature annealing** for Heusler alloy films
 - *in situ* TEM observation

Ordering Temperature for Heusler Alloys



For example, $\text{Ni}_2\text{Mn}(\text{Ga},\text{Al})$: *



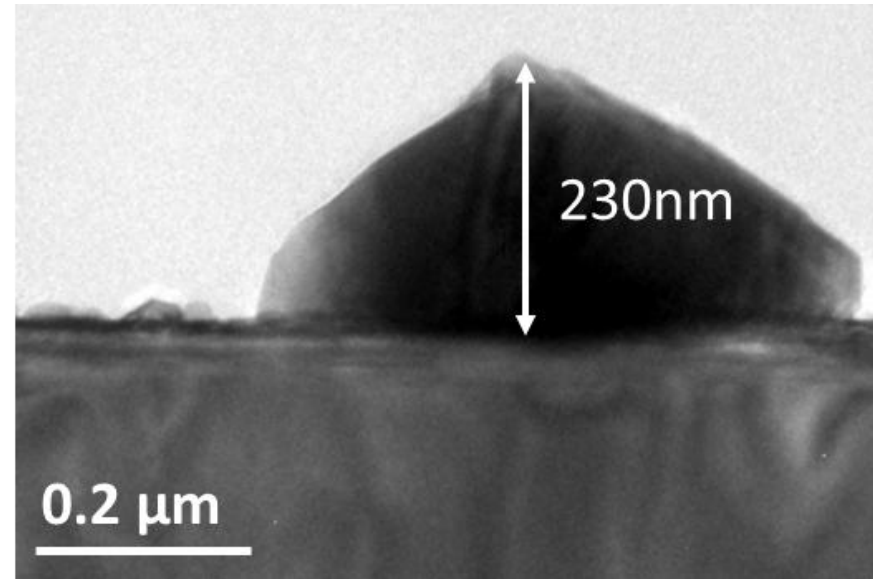
* H. Ishikawa *et al.*, *Acta Mater.* **56**, 4789 (2008);

** A. Hirohata *et al.*, *Heusler Alloys* (Springer, in press).

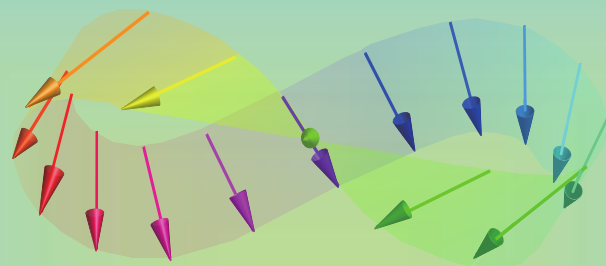


Deformation of Polycrystalline Co_2FeSi

- After annealing at 500 °C for 6 h, a 20 nm thick Co_2FeSi film crystallises 3-dimensionally.
- This forms ~ 230 nm high grain.
- This induces the discontinuity of the Co_2FeSi films.
- Lower-temperature annealing with shorter period is necessary to minimise the deformation.



Low-Temperature Crystallisation of Heusler Alloy Films



J. Sagar,¹ L. R. Fleet,¹ M. Walsh,^{1,2} K. Yoshida,^{3,4} V. K. Lazarov,¹
E. D. Boyes,^{1,2} T. Nakayama⁴ and A. Hirohata¹

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2 York **JEOL** Nanocentre

3  Nagoya University

4  **JFCC**

5  長岡技術科学大学
Nagaoka University of Technology



EPSRC EP/H026126/1
EP/M02458X/1

Engineering and Physical Sciences
Research Council



Grain Crystallisation Process

In situ TEM observation :

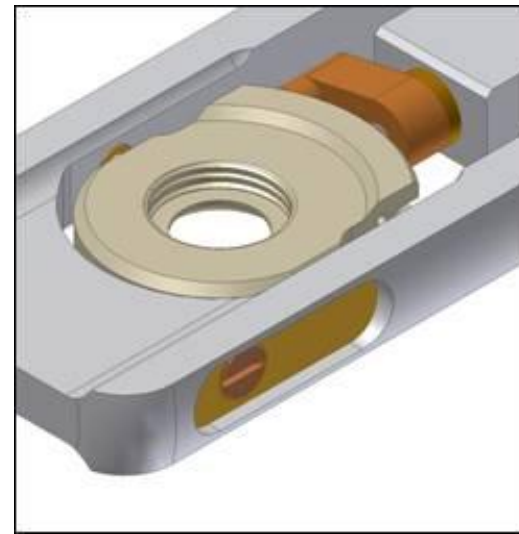


JEOL JEM-2200FS :

- Double Cs correction
- Gas introduction to sample space
- Gatan heating sample stage ($< 700^{\circ}\text{C}$)

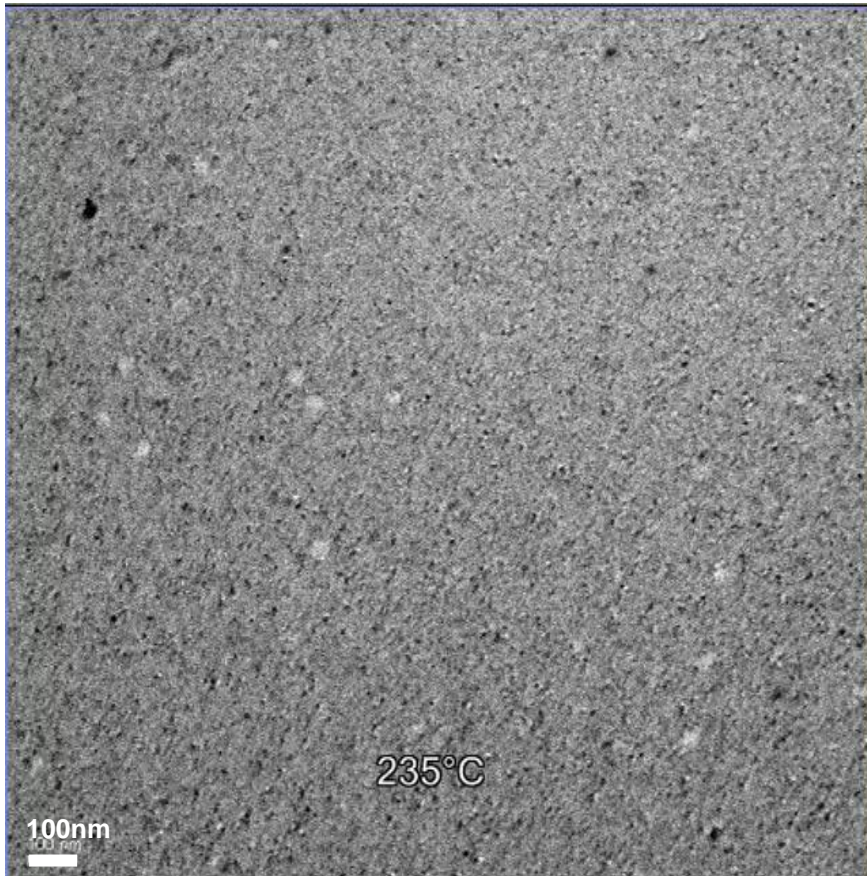
Heusler-alloy films :

- 20 nm Co_2FeSi / 2 nm Ru
- Grown on SiN TEM grids
- Continuous movie (Camtasia studio)
- Detailed HRTEM / diffractograms

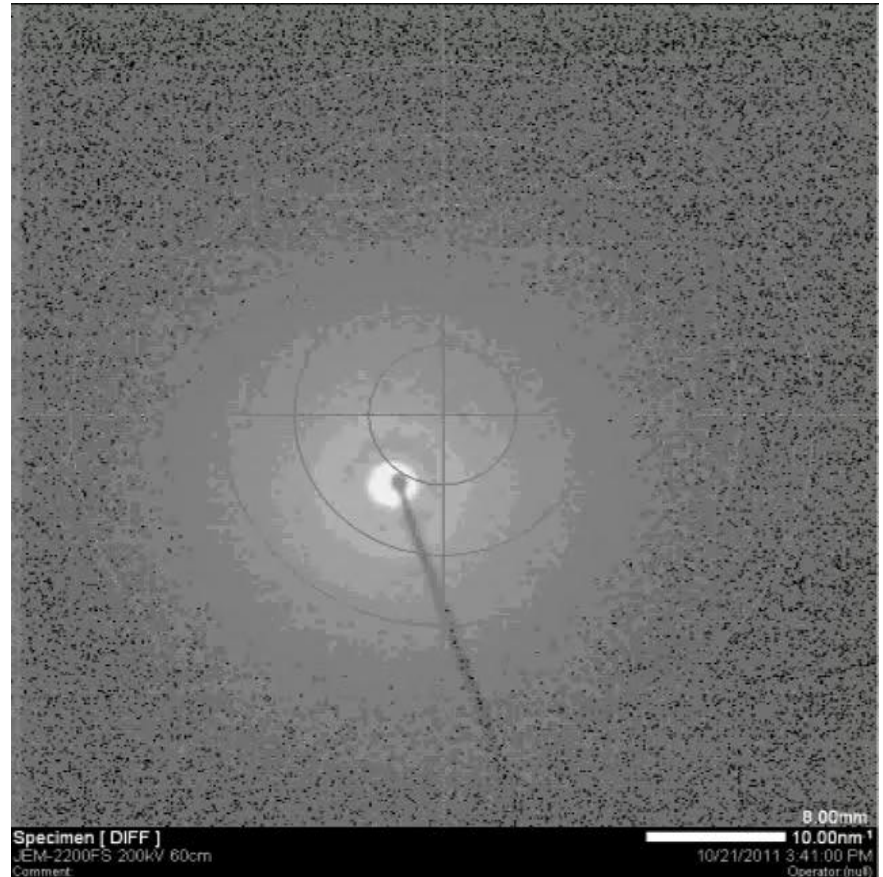




In Situ Crystallisation Process



Bright Field TEM
(235°C for 3 hours)

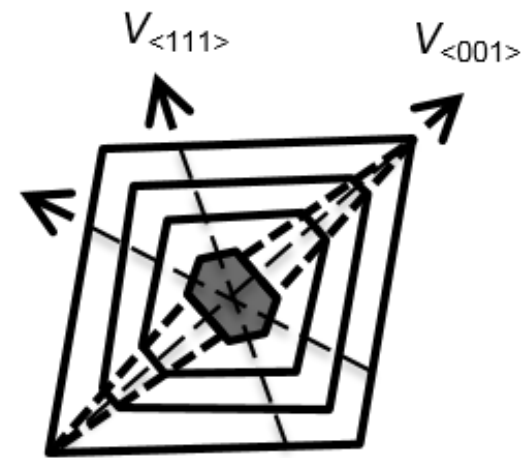
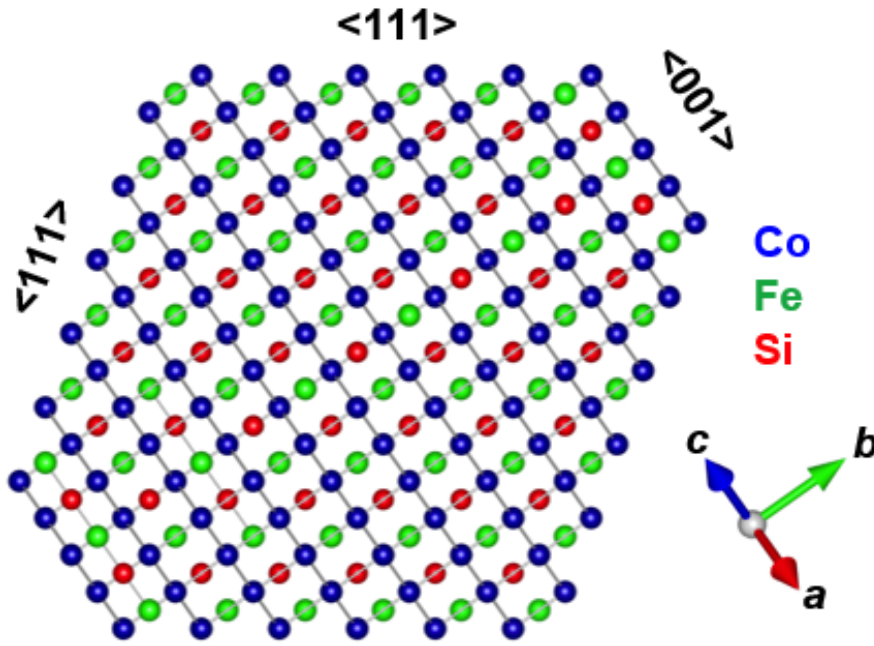
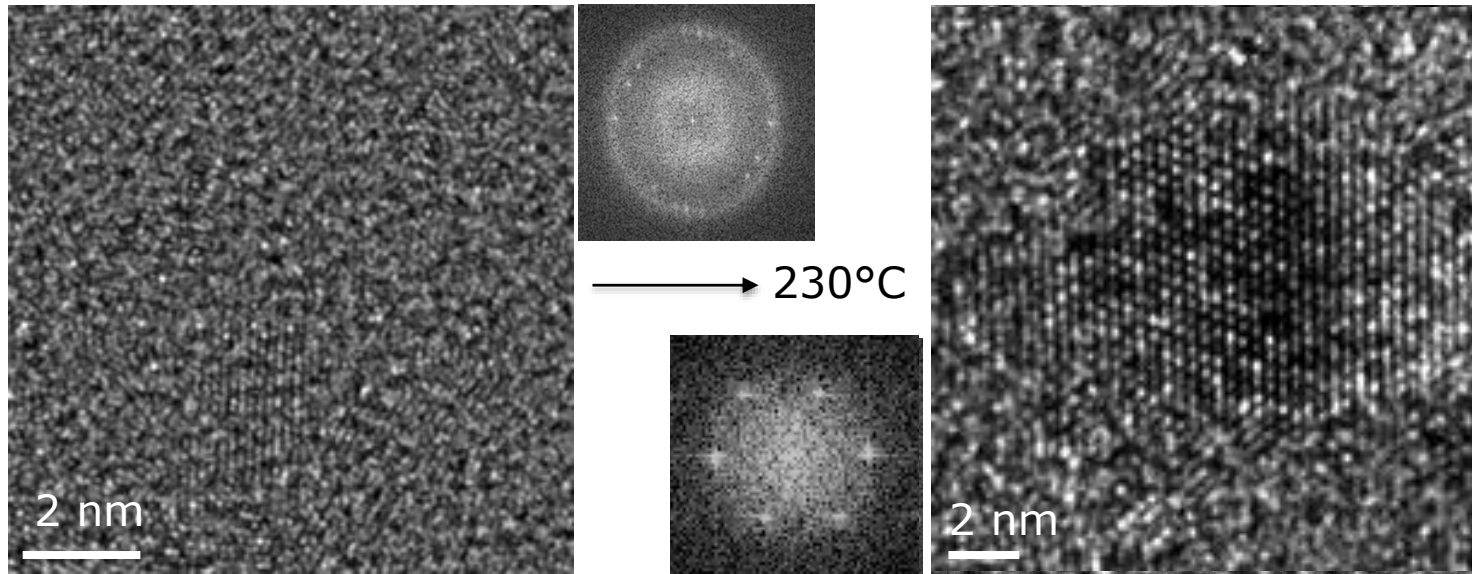


Electron diffraction pattern
(235°C for 3 hours)



Structural Analysis of Individual Grains

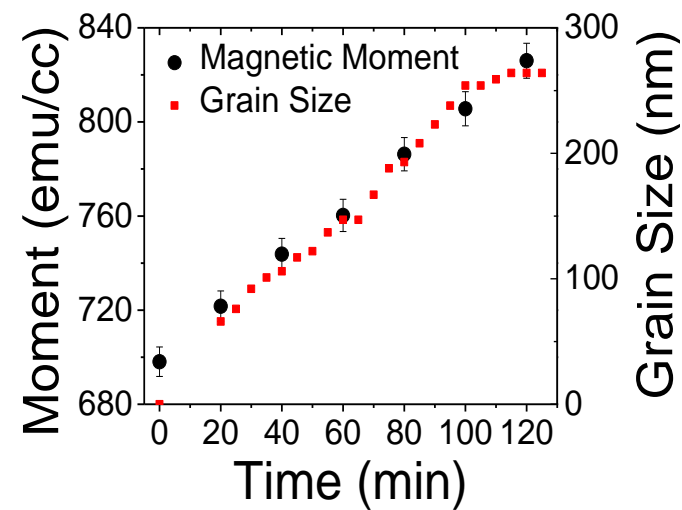
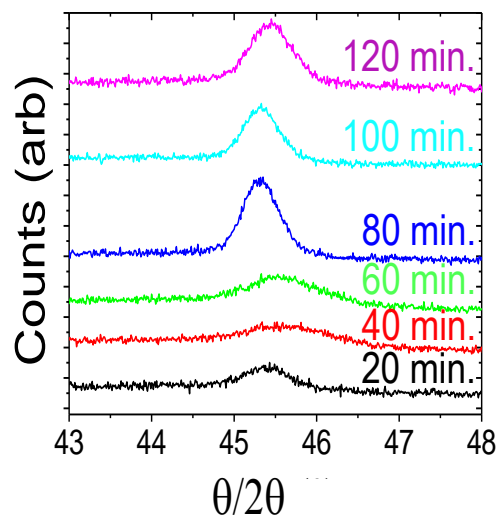
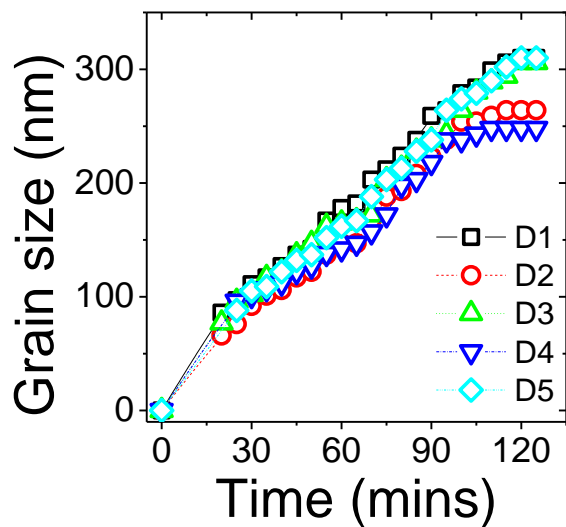
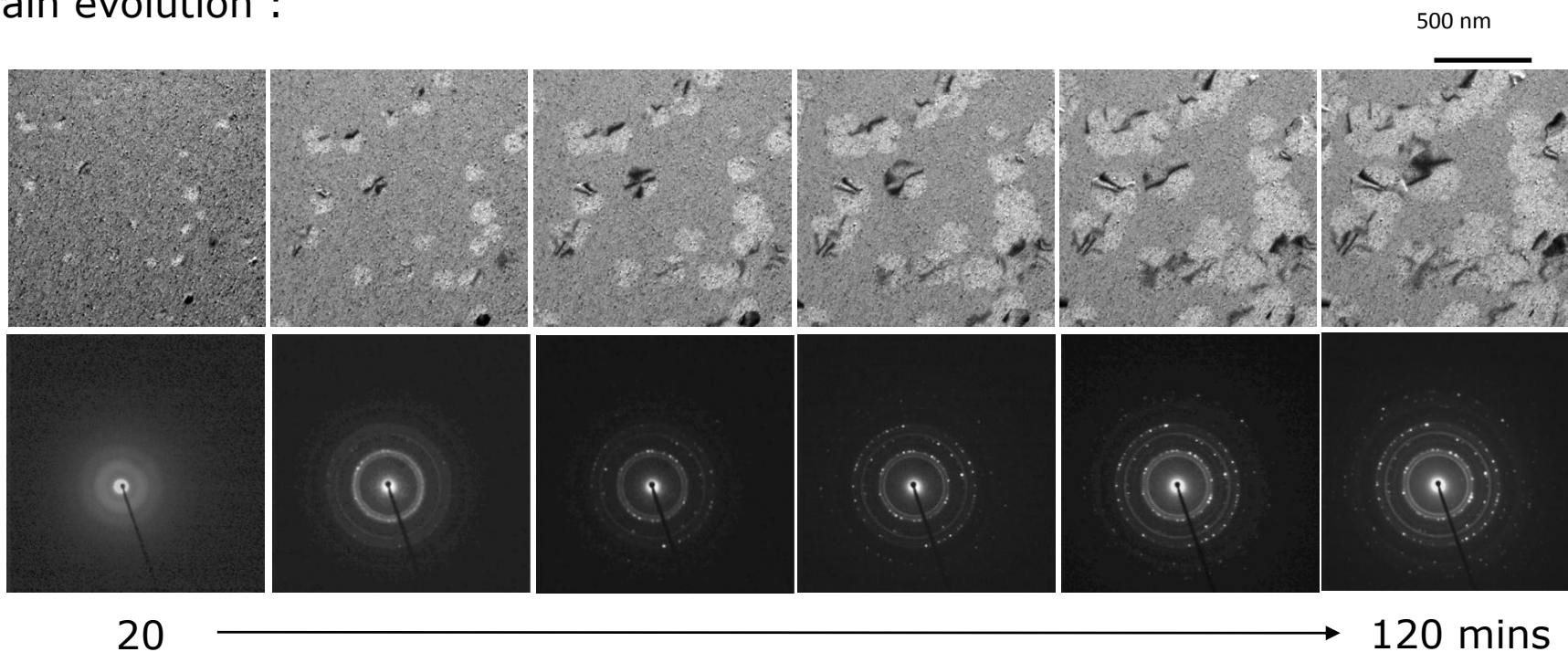
Initial grain nucleation :





Structural Analysis of Individual Grains

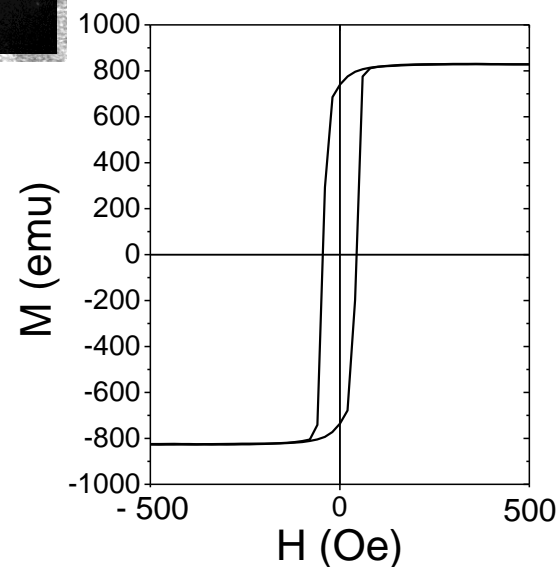
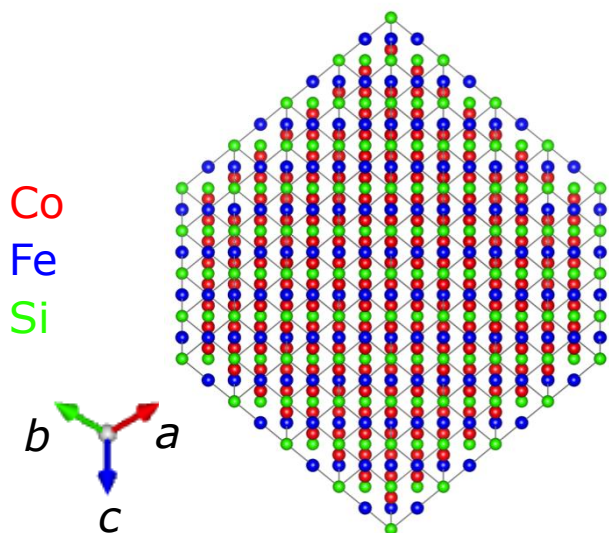
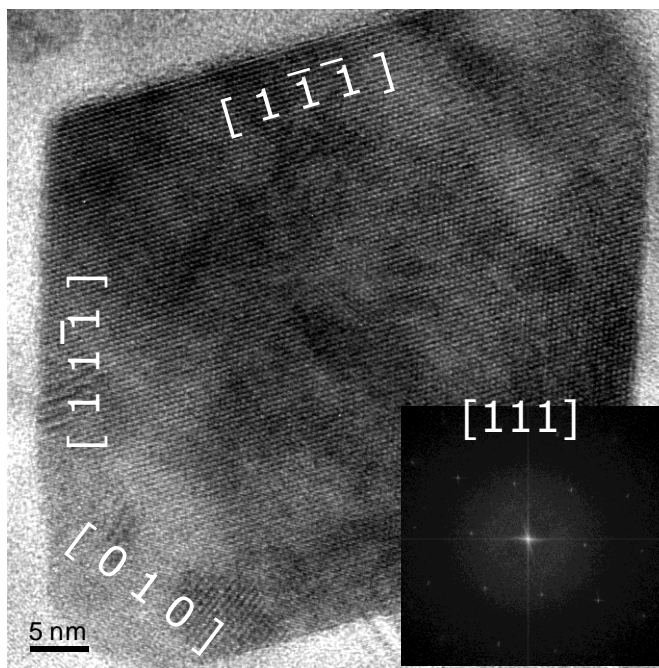
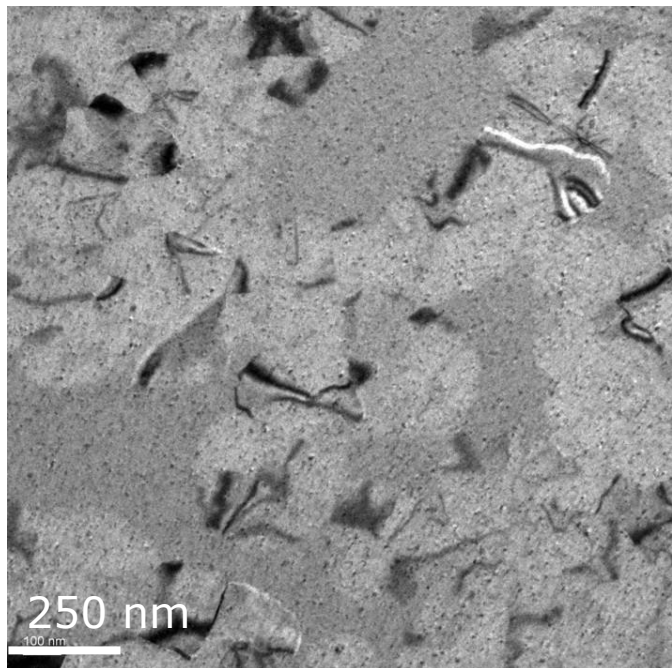
Grain evolution :





Structural Analysis of Individual Grains

Grain crystalline orientation :



* A. Hirohata *et al.*, *British Patent*, GB1402399.8.



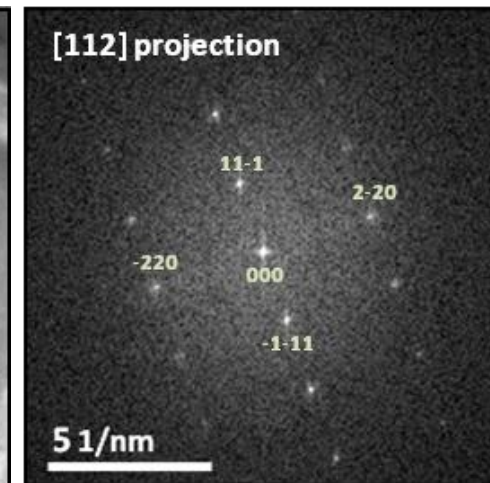
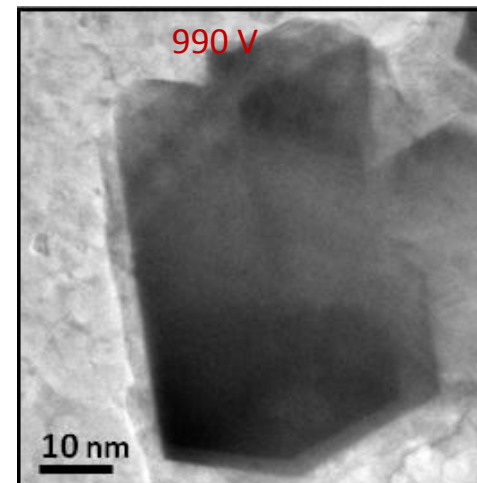
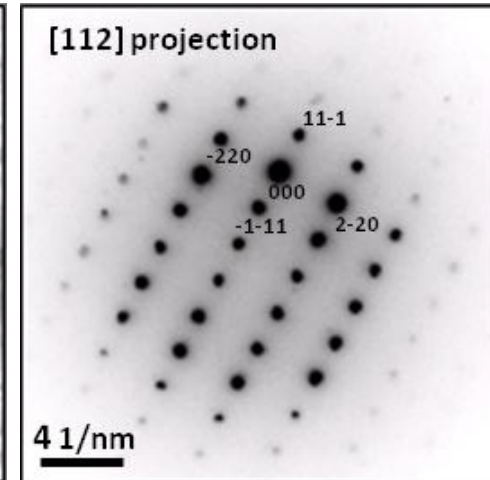
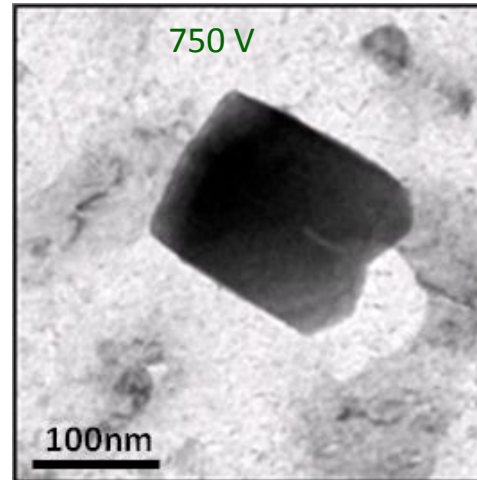
Higher Temperature Annealing

Structural analysis on Co_2FeSi grains using HRTEM :

- The analysis was performed on the 6-hour annealed sample with the **maximum grain size**.

- The grains were analysed using SAED patterns and digital diffractograms of HRTEM images.

- Each of the grains analysed showed a very well ordered structure, lying **predominantly along the [112] orientation**, possibly in the $L2_1$ phase.



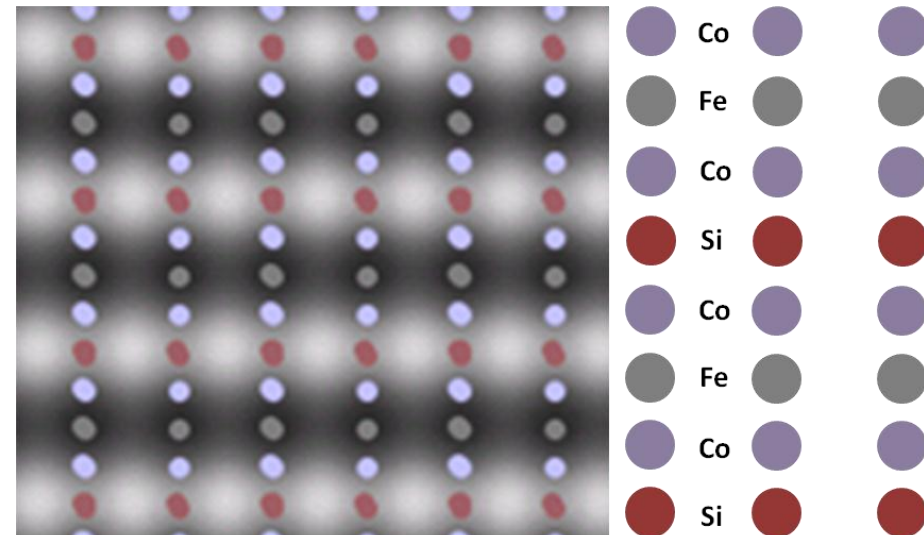
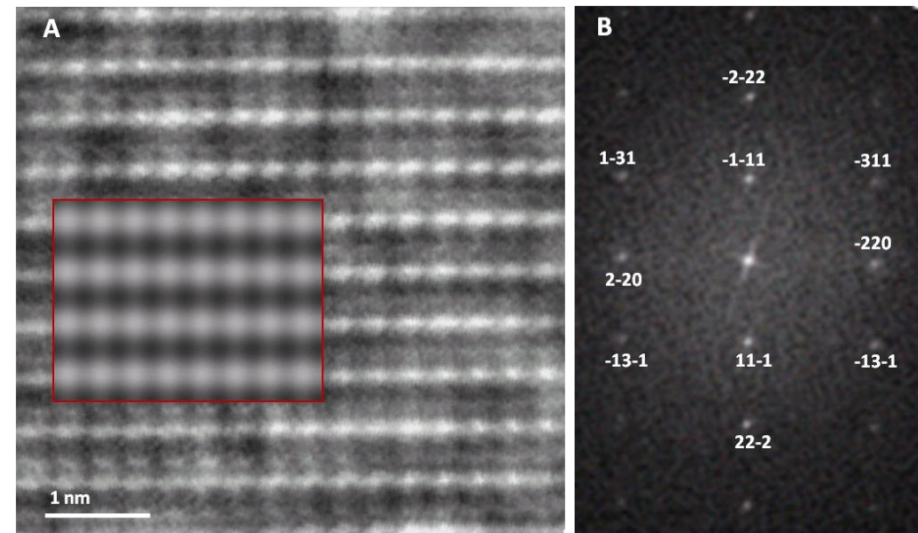


Layer-by-Layer Crystallisation

Cross-sectional analysis on Co_2FeSi films using HRTEM :

$V_B = 990$ V after 9 h annealing

- Single-nanocrystalline grains with the $L2_1$ phase were observed along the $[112]$ axis.
- Image simulations were produced using the multislice method in the electron microscopy software JEMS. *
- The grains were assumed to be in the $L2_1$ phase, orientated along the $[112]$ zone axis.
- The simulations were found to match with the experimental HRTEM images.
- This implies the grains are in the $L2_1$ phase and crystallised in a **layer-by-layer growth** mode.



* P. Stadelmann, <http://cimewww.epfl.ch/people/Stadelmann/jemsWebSite/jems.html>.



Summary on Ferromagnetic Heusler Alloys

- ❑ Small grains of ~ 10 nm begin to form at around 230°C . These grains continue to grow up to ~ 200 nm in size when held at 230°C for 3 hours.
- ❑ The lattice constant was estimated to be 0.565 nm (expected for $L2_1$ ordering).
- ❑ Further annealing does not appear to cause any significant change in the films but does effect the structure of the grains with **striping occurring after annealing over 500°C** .
- ❑ Magnetic moments gave 80 % of the theoretical maximum value.
 - Evidence for the presence of the $L2_1$ phase.
- ❑ HRTEM images and SAED patterns show **ordered grains lying in the (110) orientation**.
 - Grains crystallising in a layer-by-layer mode.

Heusler Alloy Replacement for Iridium



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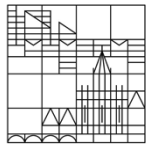


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NMP3-SL-2013-604398



SCICORP-2013

The Scarcest Material

PRODUCED BY THE FOUNDATION FOR EDUCATION, SCIENCE AND TECHNOLOGY FOR NATIONAL SET WEEK 2003

PERIODIC TABLE of the



DEPARTMENT OF
SCIENCE AND TECHNOLOGY

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- Melting point : $> 3,000^{\circ} \text{C}$
→ **Very stable**
- Almost no applications previously
- World supply : $\sim 5.8 \text{ t / yr}$
→ 87 % from South Africa
- 1 ~ 2 % in Pt and Rh ore
- **The scarecest element**
→ $4 \times 10^{-4} \text{ ppm}$
Comparisons
Nd : 33 ppm
Li : 17 ppm
Dy : 6.2 ppm
Pt : $3.7 \times 10^{-3} \text{ ppm}$
Au : $3.1 \times 10^{-3} \text{ ppm}$
Ru : $1 \times 10^{-3} \text{ ppm}$



1	H Hydrogen 1 1.01
2	Li Lithium 3 6.94
3	Na Sodium 11 22.99
4	K Potassium 19 39.10
5	Rb Rubidium 37 85.47
6	Cs Caesium 55 132.91
7	Fr Francium 87 (223)

VIII A	18	He Helium 2 4.00
		Ne Neon 10 20.18
		Ar Argon 18 39.95
		Kr Krypton 36 83.80
		Xe Xenon 54 131.29
		Rn Radon 86 (222)
		Lu Lutetium 71 174.96

Ac Actinium 89 227.03	Th Thorium 90 232.04	Pa Protactinium 91 231.04	U Uranium 92 238.03	Np Neptunium 93 237.05	Pu Plutonium 94 244.06	Am Americium 95 243.06	Cm Curium 96 247.07	Bk Berkelium 97 247.07	Cf Californium 98 251.08	Es Einsteinium 99 252.08	Fm Fermium 100 257.10	Md Mendelevium 101 258.10	No Nobelium 102 259.10	Lr Lawrencium 103 260.10
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* <http://www.atheistfrontier.com/people/dmitri-mendeleev/periodic-table-of-the-elements-for-kids.jpg>

Aim

IrMn alloy used in GMR / TMR junctions

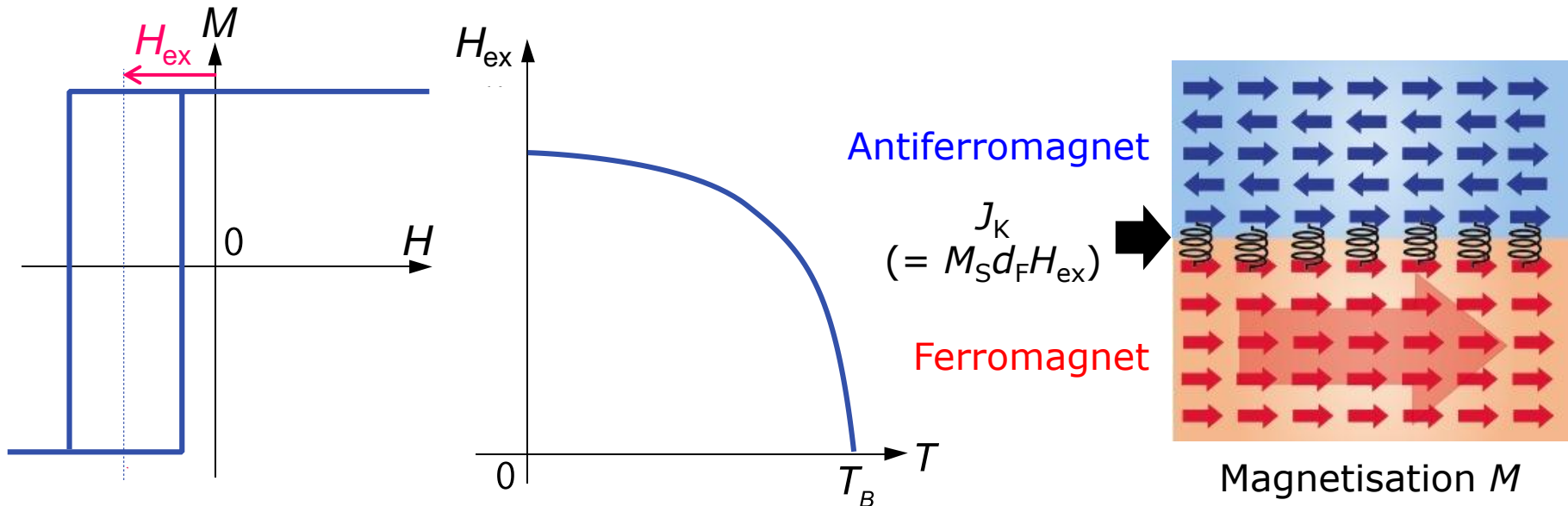
→ Antiferromagnetic Heusler alloys with common elements

Objectives

Exchange bias : $H_{\text{ex}} > 1 \text{ kOe}$ ($J_K > 1 \text{ erg/cm}^2$)

Blocking temperature : $T_B > 300 \text{ K}$

Distribution of the blocking temperature : $\sigma_{TB} < 0.3$





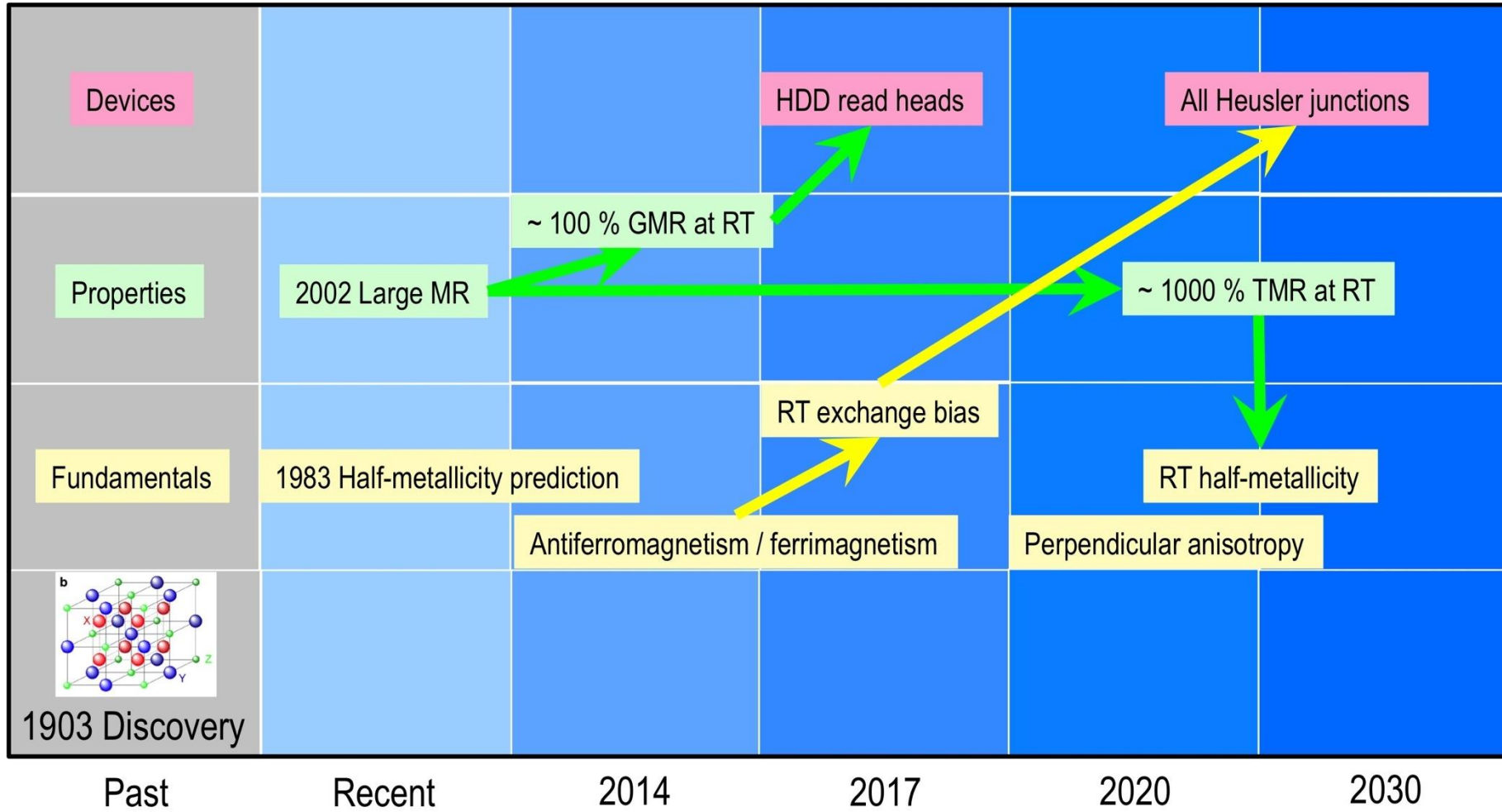
Summary on Antiferromagnetic Heusler Alloys

- ❑ Antiferromagnetic Heusler alloys have been successfully grown.
- ❑ Exchange bias has been observed at low temperature.
- ❑ Further optimisation on the crystallisation is required to achieve antiferromagnetism at room temperature.
 - Such a layer is ideal for next-generation junctions.

Polycrystalline Heusler-alloy films can

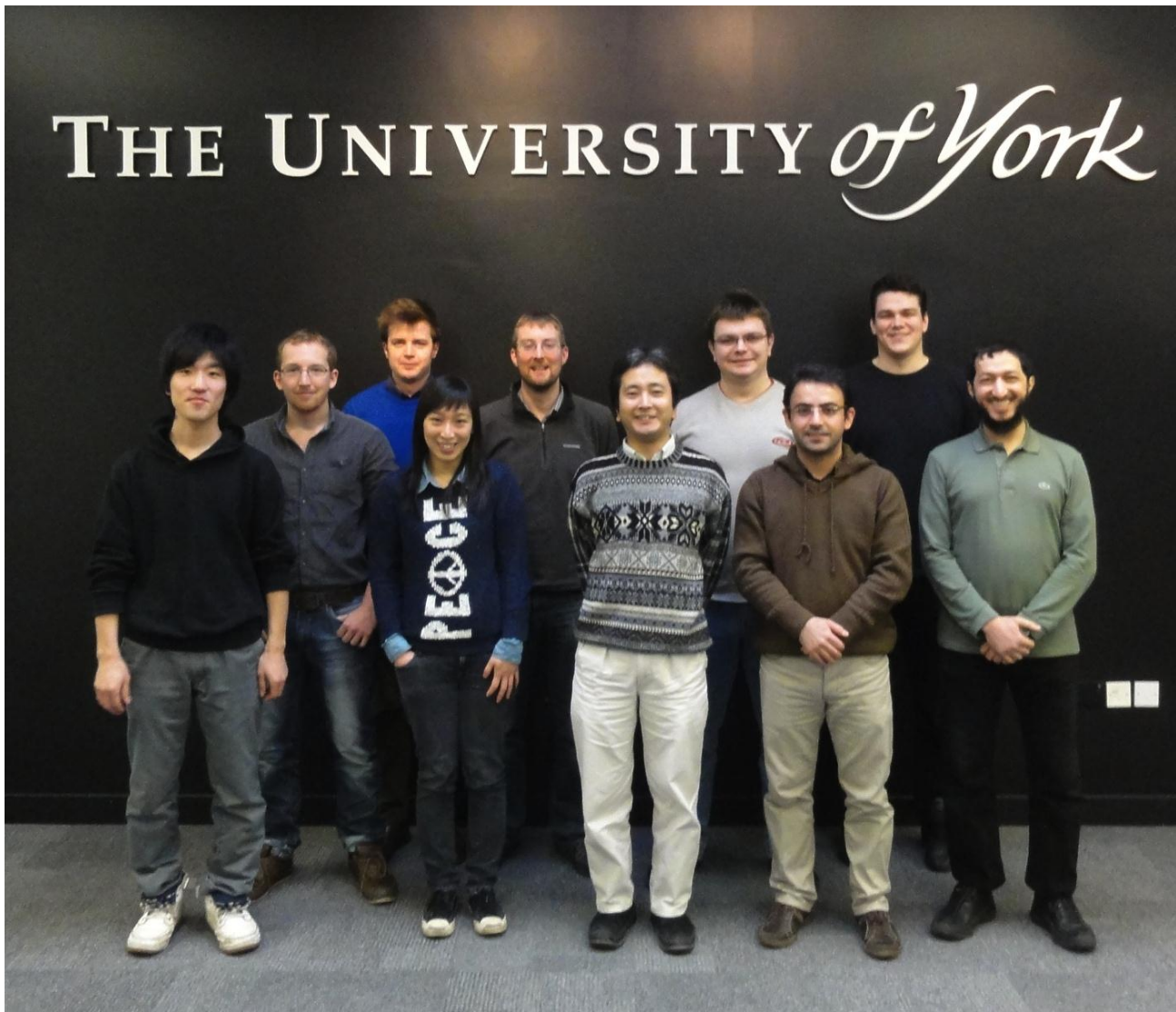
- form a junction to be reversed in a single step.
- crystallise at below 300° C compatible with the CMOS technology.
- exhibit exchange bias against a ferromagnetic layer.

Roadmap on Heusler Alloys

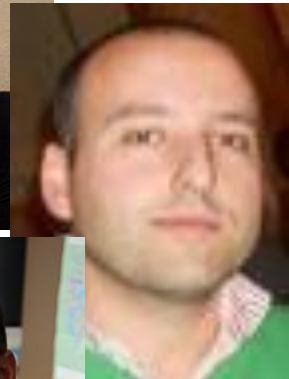





Other Group Activities



Special thanks to ...

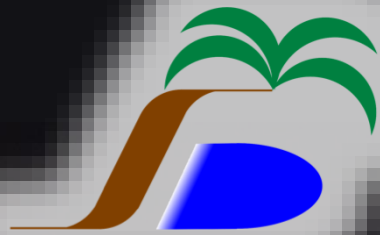


& their students
& York colleagues



13th Joint MMM-Intermag Conference

January 11-15, 2016
San Diego, California



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Abstract submission: 7 August

Thank you very much for your attention.



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